

Description of Reference Numerals on the Drawings

- 100 electron beam treatment apparatus
- 120 vacuum chamber
- 122 large-area cathode
- 124 high-voltage insulator
- 125 substrate
- 126 anode
- 127 gas manifold
- 128 cathode cover insulator
- 129 high-voltage power supply
- 130 wafer or substrate holder
- 131 low-voltage power supply
- 132 variable leak valve
- 135 vacuum pump
- 136 electron generation and acceleration region
- 138 ionization region
- 242 positive ions
- 244 electrons
- 300 feedback control circuit
- 366 integrator
- 390 sense resistor
- 392 unity gain voltage follower
- 394 variable gain resistor
- 396 amplifier
- 398 variable leak valve controller
- 400 electron beam treatment apparatus
- 410 shelf
- 415 space
- 420 vacuum chamber
- 422 large-area cathode
- 424a upper insulator

424b lower insulator
426 Anode
436 electron generation and acceleration region
510 array of holes
522 large-area cathode
524 high-voltage insulator
526 anode
560 array of holes
576 anode